

NEXTChem Process Analyzers, LLC.

On-Line SC2 Clean

Industry: Semiconductor

All wetted surfaces, in the analyzer are made of high purity teflon. Automated sample dilution is used for the measurement of highly concentrated samples commonly found in many semiconductor applications. The analyzer is housed within a white polypropylene or CPVC clean room enclosure.

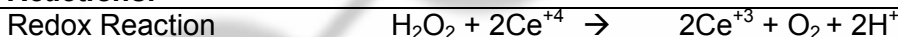


The **CHIPChem Analyzers** can provide accuracy only matched by the most precise laboratory equipment. Our reagent precision pumps deliver titrants with ± 0.001 mL reproducibility. Potentiometric analyses are utilized thus eliminating errors caused by electrode drift.

Analysis of SC2 Clean

The concentration of Hydrogen Peroxide is determined by a redox titration. Ceric sulfate is the titrant and the endpoint is determined with an ORP electrode. The concentration of Hydrochloric Acid is determined by an acid/base titration. The titrant is Sodium Hydroxide and the endpoint is found with a glass pH electrode.

Reactions:



Reagents:

0.1 N Ceric Sulfate w/ 2N Sulfuric Acid, 1 N Sulfuric Acid, 0.1 N Sodium Hydroxide

Sensor:

ORP Electrode 120 mm, Glass pH Electrode 120 mm

Detection Limits / Interferences:

Dilution: 30% – 0.024%

Non-Dilution: 233 – 0 ppm (lower detection limit 2 ppm)

Interferences: Other Acids / Other Redox Agents

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